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United States Patent [19]**Ehrlich****Patent Number: 5,310,624****[45] Date of Patent: May 10, 1994**

**[54] INTEGRATED CIRCUIT
MICRO-FABRICATION USING DRY
LITHOGRAPHIC PROCESSES**

[75] Inventor: Daniel J. Ehrlich, Lexington, Mass.

[73] Assignee: Massachusetts Institute of Technology, Cambridge, Mass.

[21] Appl. No.: 924,374

[22] Filed: Jul. 31, 1992

Related U.S. Application Data

[63] Continuation of Ser. No. 517,394, Apr. 27, 1990, abandoned, which is a continuation of Ser. No. 149,426, Jan. 29, 1988, abandoned.

[51] Int. Cl.⁵ G03C 5/00

[52] U.S. Cl. 430/322; 430/297;
430/311; 430/945

[58] Field of Search 430/297, 311, 945, 322;
427/450, 452, 455, 322

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Primary Examiner—Thori Chea

Attorney, Agent, or Firm—Thomas J. Engellenner; John V. Bianco

[57]

Dry, laser-based, lithographic techniques and systems for patterning a surface of a wafer or other substrate are disclosed. The techniques and systems are particularly adapted for automated micro-fabrication of integrated circuits on semiconductor wafers. The invention entails dry depositing a resist material on a surface of a substrate, then generating a pattern in the resist material by selectively exposing the resist material to pulsed UV laser radiation, controlling the ambient exposure of the resist material between the resist-depositing and pattern-generating steps, and, finally, transferring the pattern from the resist to the substrate or otherwise employing the pattern to transform the substrate by deposition or implantation of materials.

3 Claims, 4 Drawing Sheets

IP Bridge Exhibit 2018

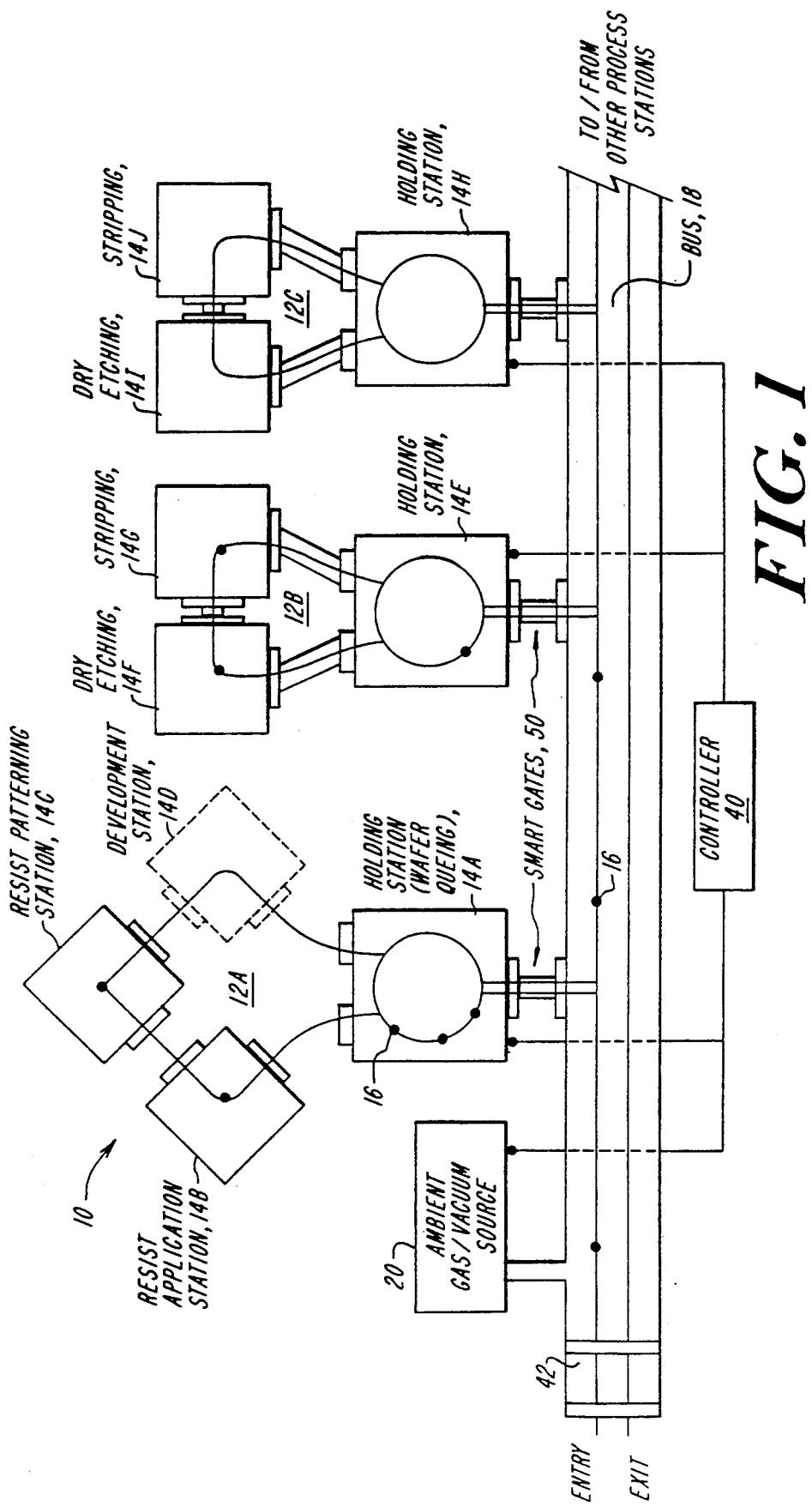


FIG. 1

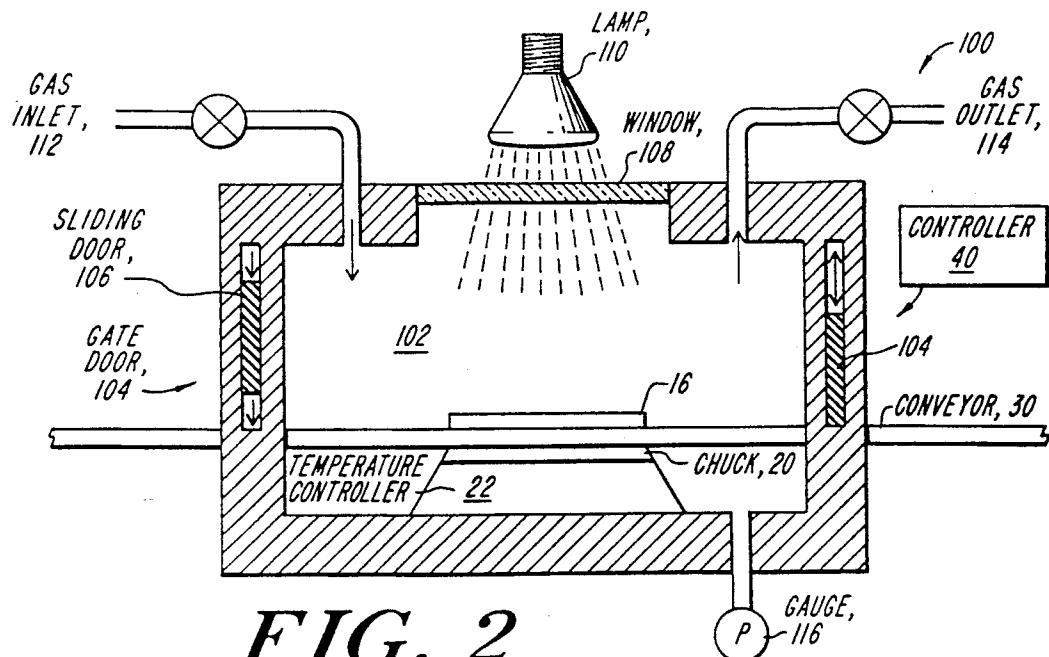


FIG. 2

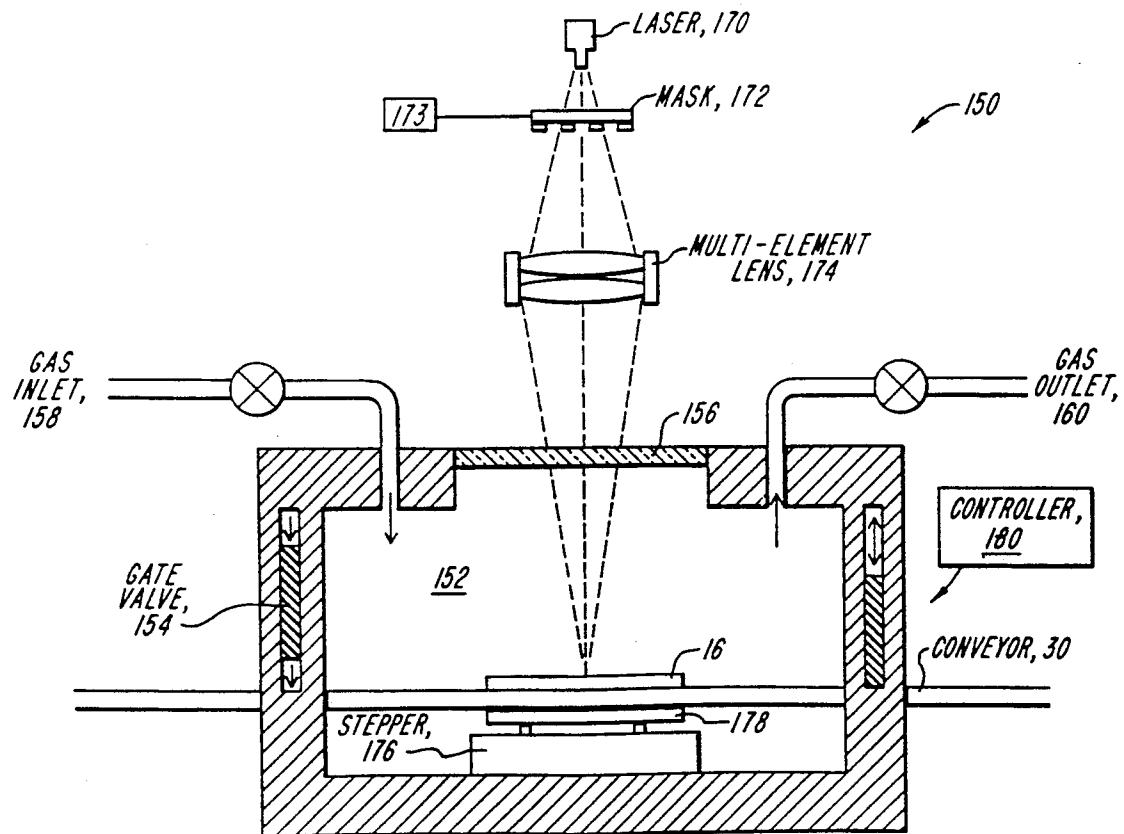


FIG. 3

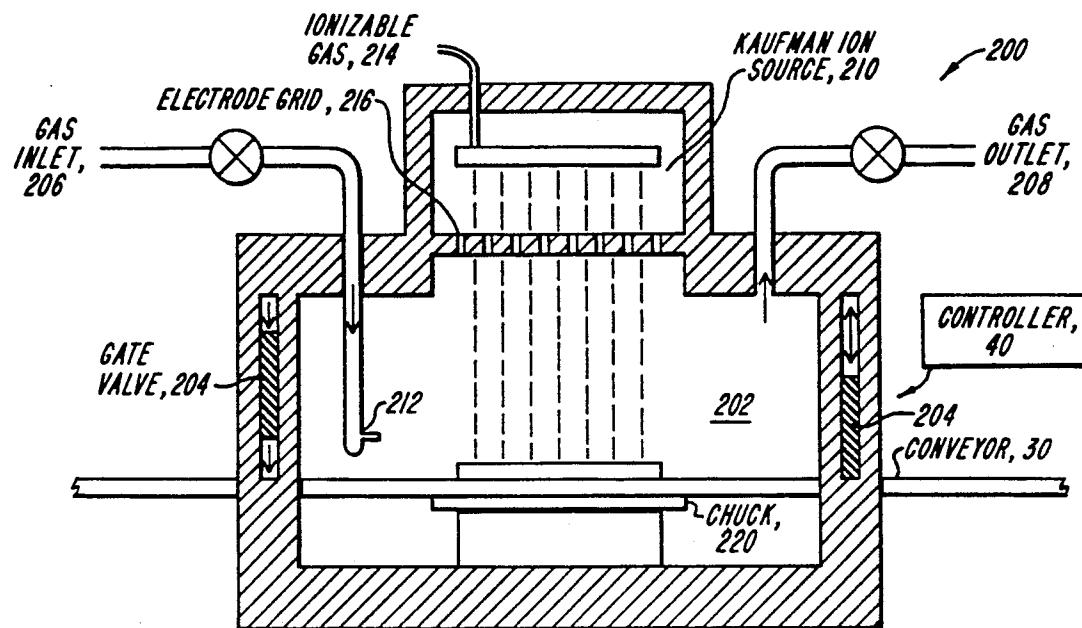


FIG. 4

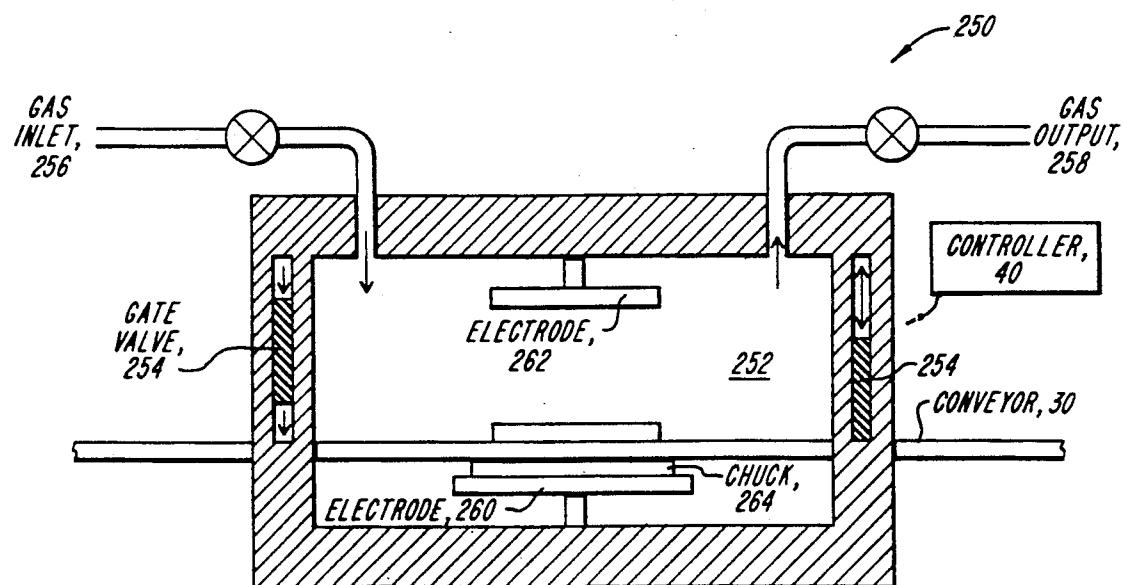


FIG. 5

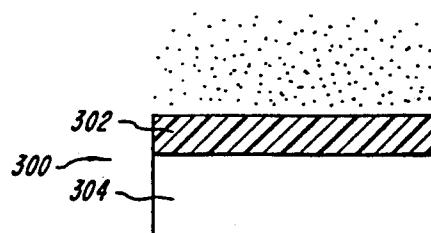


FIG. 6A

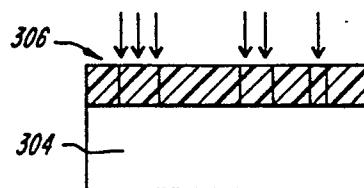


FIG. 6B

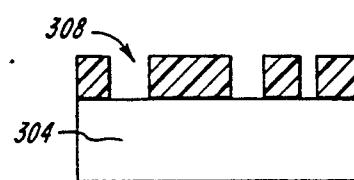


FIG. 6C

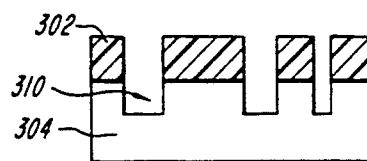


FIG. 6D

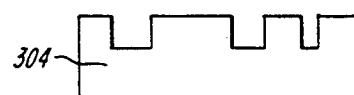


FIG. 6E

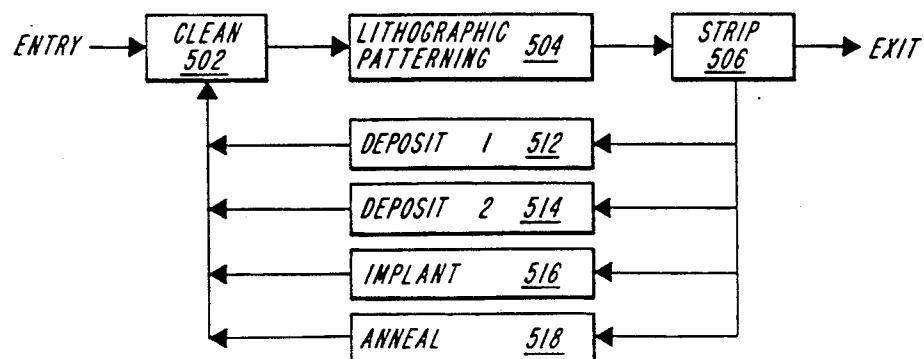


FIG. 7

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